

Docket No.: 49657-947



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Yoshikazu NAGAMURA, et al.

Serial No.: 09/779,839

Filed: February 09, 2001

Group Art Unit: 1746

Examiner: M. Kornakov

For: METHOD OF AND APPARATUS FOR WASHING PHOTOMASK AND WASHING
SOLUTION FOR PHOTOMASK

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AMENDMENT

Commissioner for Patents
Washington, DC 20231

Sir:

The following amendments and remarks are submitted in response to the Office Action
dated November 6, 2002. Please amend the application as follows:

IN THE CLAIMS:

Please amend the claims as follows:

- C1
1. (Amended) A method of washing a photomask comprising first to third steps of:
removing organic matter and metal impurities present on the surface of a photomask;
removing foreign matter adhering to said surface of said photomask with H₂ gas
dissolved water; and
drying said photomask,
wherein said photomask is a phase-shift mask including halftone mask, said H₂ gas
dissolved water contains ammonia and the concentration of said ammonia is not more than 1%.